## Supporting information for

Improving the Conductivity of sol-gel Derived  $NiO_x$  with Mixed Oxide Composite to Realize over 80% Fill Factor in Inverted Planer Perovskite Solar Cells

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**Table S1** Summary of photovoltaic parameters of the PVSCs based on different hole transport layers including PEDOT:PSS, NiO<sub>x</sub>.

Devices	J <sub>sc</sub> (mA cm <sup>-2</sup> )	$V_{oc}\left(V ight)$	FF %	PCE %	$R_{s} \left( \Omega \text{ cm}^{-2} \right)$	$R_{sh}(k\Omega\;cm^{-2})$
PEDOT:PSS	20.66	0.90	71	13.2	2.54	0.727
NiO <sub>x</sub>	20.8	1.03	73	15.6	5.25	0.706



Figure S1. XRD patterns of GO and GO annealed at 300 °C.



Figure S2. XPS spectra of (a) GO and (b) GO annealed at 300 °C.

The electrochemical impedance spectroscopy (EIS) was conducted under dark with a bias close to  $V_{oc}$  to further investigate the charge transport in the devices. Figure S1 shows the Nyquist plots collected over the frequency range of 1Hz to 1MHz. It is well known that the high frequency semicircle gives detailed electrical process about charge transport at the interfaces between charge extraction layer and perovskite layer. By fitting the plots with the equivalent circuit shown in the inset of Figure S1, the NiO<sub>x</sub>:rGO based device exhibits a reduced charge transport resistance (83.2  $\Omega$ ) compared to the pure NiO<sub>x</sub> counterpart (269  $\Omega$ ) suggesting that introducing the rGO sheets into the NiO<sub>x</sub> matrix is an effect approach to improve its charge extraction efficiency.



**Figure S3.** Typical Nyquist plots of  $NiO_x$  and  $NiO_x/rGO$  based devices under dark with a bias closed to the  $V_{oc}$ .



Figure S4. UV-vis absorption spectra of NiOx and NiOx:rGO (2%) films.

To further evaluate the charge recombination process of NiO<sub>x</sub> and NiO<sub>x</sub>:rGO based devices, light dependence  $V_{oc}$  was carried out (**Figure S2**). Normally, the slope of  $V_{oc}$  versus the natural logarithm of light intensity reveals the dominant recombination mechanism in the device. The slope of kT/q indicates bimolecular recombination while the slope larger than kT/q suggests that trap-assisted recombination occurs. The NiO<sub>x</sub>:rGO based device have smaller slope of 1.32 kT/q compared to the pure NiO<sub>x</sub> based device (1.97 kT/q), indicating that the trap-assisted recombination is effectively supressed in NiO<sub>x</sub>:rGO based device. These results agree well with the TPC and TPV results.



Figure S5. Light dependence V<sub>oc</sub> of NiO<sub>x</sub> and NiO<sub>x</sub>:rGO based devices.



**Figure S6** Shelf-lifetime of the NiO<sub>x</sub>:rGO based PVSC.